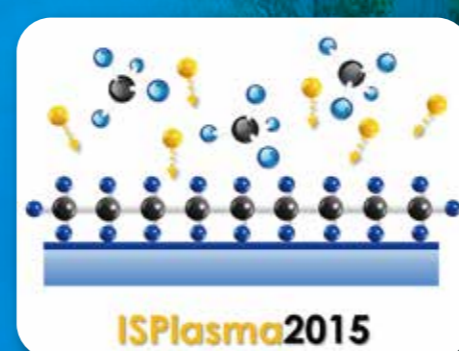


7th International Symposium on Advanced Plasma Science
and its Applications for Nitrides and Nanomaterials /
8th International Conference on Plasma-Nano Technology & Science



ISPlasma2015 IC-PLANTS2015



March 26-31, 2015
Nagoya University, Japan
<http://www.isplasma.jp/>

Chairperson : Nagahiro Saito, Nagoya University

Vice-Chairperson : Keiji Nakamura, Chubu University

Akihiro Wakahara, Toyohashi University of Technology

Noritsugu Umehara, Nagoya University

Sponsored by :

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Co-sponsored by :

Nagoya University, Nagoya Institute of Technology, Meijo University, Chubu University, Aichi Science & Technology Foundation,
The Japan Society of Plasma Science and Nuclear Fusion Research, The Japanese Association for Crystal Growth

Related Fields

Plasma Science • Plasma Source • Modeling and Simulation • Thin Film Deposition Process • Etching Process • Atmospheric-pressure plasma • Solution Plasma
• Advanced Plasma Measuring Technology • Plasma for Clean Energy • Plasma Biology and Medicine • Plasma for Nanotechnology

Functional Semiconductors • Crystal Growth of GaN and Related Materials • SiC/Diamond • Optical Devices • MBE Growth of Nitrides • Power device • Electron Devices

Nanomaterials and Micro fabrication • Nano structured material • Catalyst/Battery • Solar Cell • Environmental materials • Micro-TAS

Surface Functionalization • Hard coating • Thin Films by chemical process • Biosurface and biointerface • Functional thin films

Special Issue

Selected papers will be published in a special issue of Jpn. J. Appl. Phys. (JJAP). Submission Deadline : April, 2015

Special Speaker



Nobel Laureate in Physics

Prof. Hiroshi AMANO

Nagoya University

March 29, 2015

14:00 - 15:20

Toyoda Auditorium, Nagoya University



Plenary Speakers

Prof. Yasuhiko ARAKAWA (The University of Tokyo, Japan)

Prof. Vincent M. DONNELLY (University of Houston, USA)

Prof. Hiroyuki MATSUNAMI (Kyoto University, Japan)

Prof. Ravi SILVA (University of Surrey, United Kingdom)

Prof. Kazunari DOMEN (The University of Tokyo, Japan)

Prof. Ulf HELMERSSON (Linkoping University, Sweden)

Prof. Masaharu SHIRATANI (Kyushu University, Japan)

Dr. Koji SUMITOMO (NTT Basic Research Laboratories, Japan)

Sessions

Plasma Science

- A1 Plasma Engineering
- A2 Plasma Deposition
- A3 Plasma Medicine
- A4 Plasma Applications
- A5 Atmospheric Pressure Plasma
- A6 Solution Plasma

Functional Semiconductors

- B1 Nitride Process
- B2 Application of Nitride Semiconductors
- B3 SiC • Diamond • Other Related Materials

Nanomaterials and Nano/Micro Fabrication

- C1 Nanostructured and Nanocomposite Materials
- C2 Catalyst / Battery
- C3 Solar Cell
- C4 Environmental and Energy Materials
- C5 Microfluidics, Nanofluidics, and microTAS

Surface Functionalization

- D1 Hard Coating
- D2 Wet Coating
- D3 Functional Thin Films
- D4 Biosurface

Registration Advanced Online Registration is required.

General Student

Registration Fee: Early Registration — JPY 45,000 JPY 15,000
(Before Feb 16, 2015)

On-site Registration — JPY 50,000 JPY 20,000

Banquet Fee (On March 29, 2015) — JPY 10,000 JPY 10,000
(at Port of Nagoya Public Aquarium)

* Refunds cannot be made at any reason.

Contact

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